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| Substitute for form 1449A/PTO | | | Complete If Known | | |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i> | | | Application Number | 10/616,603 | |
| | | | Filing Date | 10 July 2003 | |
| | | | First Named Inventor | Christophe Pierrat et al. | |
| | | | Group Art Unit | | |
| | | | Examiner Name | | |
| Sheet | 1 | of | 2 | Attorney Docket Number | FTIS 1001-1 |

| U.S. PATENT DOCUMENTS | | | | | | |
|-----------------------|-----------------------|----------------------|-----------------------------------|---|--|---|
| Examiner Initials* | Cite No. ¹ | U.S. Patent Document | | Name of Patentee or Applicant of Cited Document | Date of Publication of Cited Document MM-DD-YYYY | Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear |
| | | Number | Kind Code ² (If known) | | | |
| UX | A1 | 5,121,256 | | Corle et al. | 06-09-1992 | |
| UX | A2 | 5,469,299 | | Nagano | 11-21-1995 | |
| UX | A3 | 5,982,558 | | Further et al. | 11-09-1999 | |
| UX | A4 | 6,198,576 | | Matsuyama | 03-06-2001 | |
| UX | A5 | 6,522,484 | | Schuster | 02-18-2003 | |
| | A6 | | | | | |
| | A7 | | | | | |
| | A8 | | | | | |
| | A9 | | | | | |
| | A10 | | | | | |
| | A11 | | | | | |
| | A12 | | | | | |
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| | A14 | | | | | |
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| | A17 | | | | | |
| | A18 | | | | | |
| | A19 | | | | | |
| | A20 | | | | | |

| FOREIGN PATENT DOCUMENTS | | | | | | | | |
|--------------------------|---------------|-------------------------|---------|--------------------------|--|--|--|----|
| Examiner Initials* | Cite No. 1 | Foreign Patent Document | | | Name of Patentee or Applicant of Cited Document | Date of Publication of Cited Document MM-DD-YYYY | Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear | T6 |
| | | Office3 | Number4 | Kind Code5 (If known) | | | | |
| | B1 | | | | | | | |
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| | B10 | | | | | | | |

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| Examiner Signature <i>Donald H. Charles</i> | Date Considered 09/30/05 |
|---|--------------------------|

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 2 of 2

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| First Named Inventor | Christophe Pierrat et al. |
| Group Art Unit | |
| Examiner Name | |
| Attorney Docket Number | FTIS 1001-1 |

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS

| Examiner Initials* | Cite No. ¹ | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | T ² |
|--------------------|-----------------------|---|----------------|
| WD | C1 | FRENCH, ROGER H., et al., "Fluoropolymers for 157nm Lithography: Optical Properties from VUV Absorbance and Ellipsometry Measurements," SPIE Proceedings, Microlithography 2000, 12 pages. | |
| WD | C2 | FLAGELLO, DONIS G., et al., "High-numerical-aperture effects in photoresist," Applied Optics 36(34) (1 Dec 1997) 8944-8951. | |
| WD | C3 | FRENCH, ROGER H., et al., "Materials Design and Development of Fluoropolymers for Use as Pellicles in 157nm Photolithography," Optical Microlithography XIV, Proceedings of SPIE vol. 4346 (2001). | |
| WD | C4 | PIERRAT, CHRISTOPHE, et al., "The MEF Revisited: Low k1 Effects versus Mask Topography Effects," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (25 Feb 2003). | |
| WD | C5 | CHIBA, YUJI, et al., "New generation projection optics for ArF lithography," Optical Microlithography XV, Proceedings of SPIE Vol. 4691 (2002), 679-686. | |
| WD | C6 | BAEK, SO-YEON, et al., "Simulation Study of Process Latitude for Liquid Immersion Lithography," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (27 Feb 2003), 11 pages. | |
| WD | C7 | PENDRY, J.B., et al., "Near-field lenses in two dimensions," J. Phys.: Condens. Matter 14 (2002) 8463-8479. | |
| WD | C8 | OBER, CHRISTOPHER K., "Polymer Surfaces and Surface Analysis," Nanobiotechnology MSE 563/AEP 663 (2000), 43 pages. | |
| WD | C9 | HAFEMAN, SCOTT, et al., "Simulation of imaging and stray light effects in immersion lithography," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (27 Feb 2003), 13 pages. | |
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Examiner
Signature

David Charles Davis

Date

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